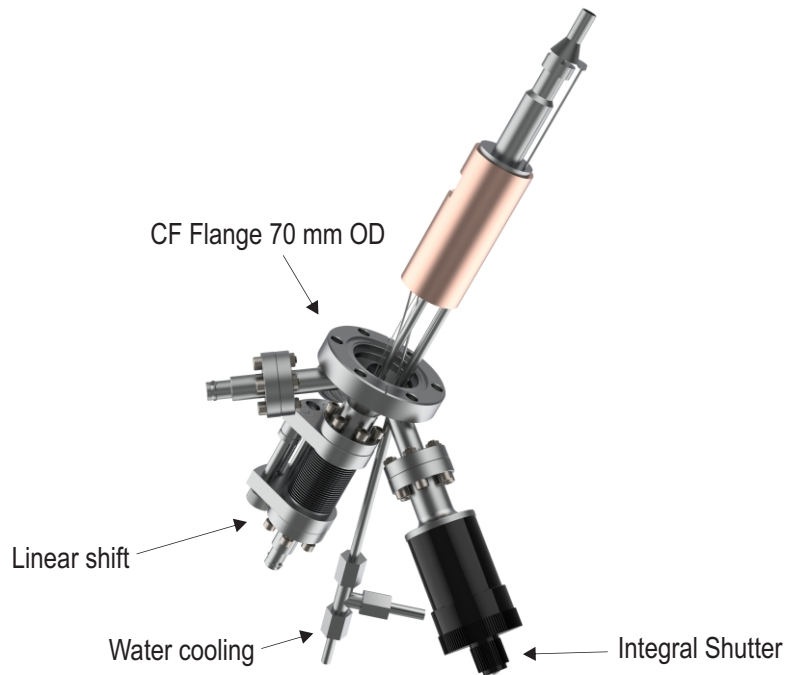


Electron Beam Evaporator

Model:EB-Evap40



Description

The electron beam evaporator, model EB-Evap 40 is a compact vapour source of almost any solid state material that is needed for deposition of thin film on substrate .

The temperature range for material evaporation is from 100 °C to 2300 °C.

Evaporation is directly from 2 mm diameter rod or indirectly from the small crucible.

The unit is very compact and suitable for any UHV system



Canada: 200 Stronach Cres., London, Ontario, N5V3A1
USA: 6405 Inducon Drive West, Sanborn (Niagara County), NY, 14132
TEL. (519) 457-0878, FAX (519) 457-0837
E-mail: info@ocivm.com
Website: www.ocivm.com

Features:

Mounting flange: DN40CF with 190 mm vacuum insertion length and 35 mm O.D.

Water cooling: internal water flow reducing components outgassing

Filament: Tungsten filament with range 2- 2.4 A

Voltage range: 0 - 1500 V

Evaporating Source: Rod 2 mm diameter with 25 mm wire feed range

Crucible materials: Ma, Ta, W, Graphite

Liner Material options: BN, Quartz, Alumina

Working distance: 50 mm – 100 mm range

Shutter: integral manual shutter